

Amendment to and Listing of the Claims:

1-4 (Canceled)

5. (New) A liquid dust control composition consisting essentially of approximately by weight:

- (a) 0.1% to 5.0% of at least one anionic surfactant;
- (b) 0.025% to 1.0% of a dust control agent, which is choline chloride or quaternized alkylolamine methosulfate having about 2 to about 18 carbon atoms;
- (c) a water soluble propylene glycol ether cosurfactant; and
- (d) water.

6. (New) The composition of claim 5 wherein said anionic surfactant is a sulfate surfactant.

7. (New) The composition of claim 6 further comprising a C₂-C₄ alkanol.

8. (New) A liquid dust control composition comprising approximately by weight:

- (a) 0.1% to 5.0% of at least one anionic surfactant;
- (b) 0.025% to 1.0% of a dust control agent, which is choline chloride or quaternized alkylolamine methosulfate having about 2 to about 18 carbon atoms;
- (c) a water soluble propylene glycol ether cosurfactant; and
- (d) the balance being water

said composition being free of polyvinyl pyrrolidone having a molecular weight of about 10,000 to 100,000, N-octyl-2-pyrrolidone, N-dodecyl-2-pyrrolidone, polysiloxane polyorgano betaine copolymer, diquaternary polydimethyl siloxane, copolymer of polyvinyl pyrrolidone/polyvinyl-imidazole copolymer, polyvinyl pyrrolidone/polyacrylate copolymer, an alkoxy silane-quaternary compound, cyclotetra dimethyl siloxane, cyclopenta dimethyl siloxane, diethyl cyclohexyl amine salt of lauryl sulfate, anionic R_fCH₂CH₂SO₃X wherein R_f is F-(CF₂CF₂)₃₋₈ and X=H or NH₄, nonionic R_fCH₂CH₂O(CH₂CH₂O) wherein R_f is F-(CF₂CF₂)₃₋₈, and amphoteric R_fCH₂CH(OCOCH₃)CH₂N⁺(CH₃)₂CH₂CO₂⁻, wherein R_f is F-(CF₂CF₂)₃₋₈.

9. (New) The composition of claim 8 wherein said anionic surfactant is a sulfate surfactant.

10. (New) The composition of claim 9 further comprising a C₂-C₄ alkanol.